

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

Application Serial No. ....10813543  
Filing Date .....March 3, 2004  
Confirmation No. .... 8087  
Inventor..... Gealy, F. Daniel  
Assignee .....Micron Technology, Inc.  
Group Art Unit ..... 1792  
Examiner ..... Chen, Keath T.  
Attorney's Docket No. .... MI22-3685  
Title:..... Method for Reducing Physisorption During Atomic Layer Deposition

**INFORMATION DISCLOSURE STATEMENT**

References - - See attached Form PTO/SB/08

The attached Form PTO/SB/08 is submitted in compliance with 37 C.F.R. §§ 1.56, 1.97 and 1.98, and your attention is directed to the references listed on the attached Form PTO/SB/08. No admission is made regarding whether the submitted references are prior art.

A fee in the amount of \$180.00 will be paid to cover the fee specified under 37 C.F.R. § 1.17(p).

Citation of these references is respectfully requested.

Respectfully submitted,

Dated: 6/30/08

By:   
Robert C. Hyta  
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